

§6. Electrostatic Coupling of Antenna and the Shielding Effect in Inductive RF Plasmas

Nakamura, K., Shirakawa, T., Toyoda, H., Sugai, H. (Faculty of Eng., Nagoya Univ.)
Kuroda, T.

Recently, much attention has been paid to an inductively coupled RF plasma as an innovative plasma source for neutral beam production[1] as well as material processing. Even in such an inductive plasma, the capacitive coupling from a RF antenna has been observed[2] and leads to the sputtering of the insulating wall materials contacting the antenna. In this study, the capacitive coupling from an antenna has been quantitatively estimated, measuring a dc self-bias voltage induced on the surface of the insulator by electrostatic fields.[3]

Figure 1 shows the spatial distribution of dc self-bias voltage V_{DC} along a 1 turn loop antenna of 10 ~ 11 cm in radius for two different thickness of antenna insulating cover, where θ is the azimuthal position along the circular antenna as defined in Fig.1. A large negative bias of ~130 V was observed at the input RF power of 500 W in the case of the antenna covered with thin insulator of 1 mm in thickness. For thick insulator of 8.8 mm in thickness, the bias V_{DC} considerably decreased but ion energy E_i bombarding the insulator surface was still as high as ~ 40 eV since $E_i = e(V_p - V_{DC})$ and the plasma potential $V_p = \sim 20$ V. Concerning the azimuthal distribution of V_{DC} the bias becomes more negative at the point on the RF feed side ($\theta \sim 350^\circ$) than on the ground side ($\theta \sim 10^\circ$) of the antenna loop.

On the other hand, the power dependence of V_{DC} was examined for the thick insulator antenna and the thin insulator antenna where $\theta = 330 \sim 350^\circ$. As shown in Fig.2, the bias becomes increasingly negative with increasing RF power while the plasma potential remains almost constant at ~ 20 V and $\kappa T_e = 2.5 \sim 4$ eV.

Finally, in order to suppress the electrostatic coupling effectively, an electrostatic shield was formed, and its effect on the self-bias voltage was examined for the thick insulator antenna. The value of V_{DC} becomes positive and close to the floating potential given by a Langmuir probe. Thus, the shield effect was clearly recognized in comparison with the unshielded antenna.

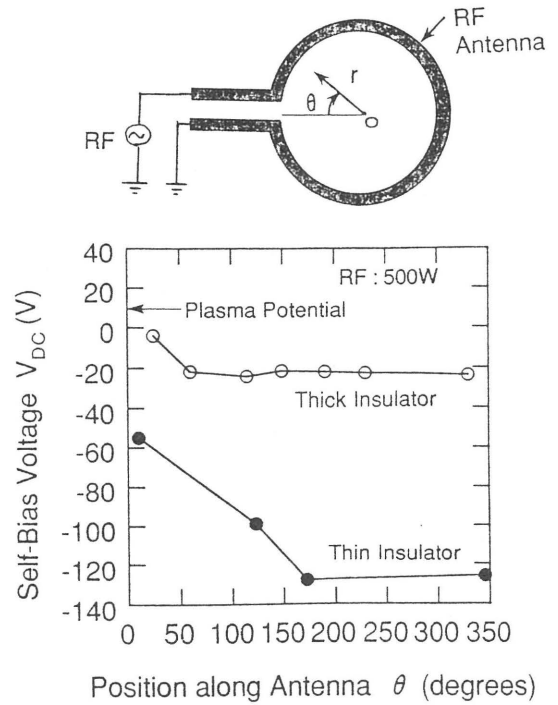


Fig. 1. Self-bias voltage along the antenna covered with thin insulator and thick insulator.

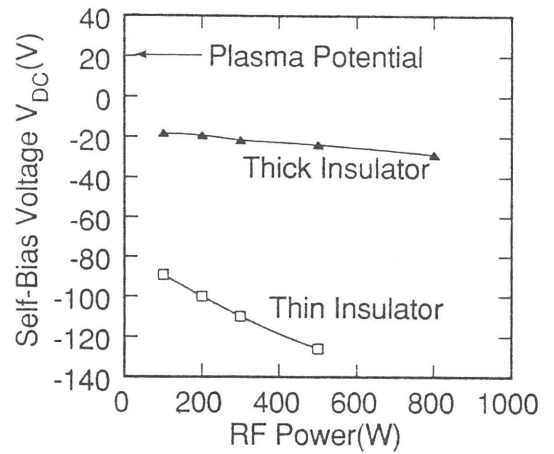


Fig. 2. Self-bias voltage v.s. rf power for the antenna with thin and thick insulators.

References

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